

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In Re Application of:

Robert David Allen et al.

Examiner: John S.Y. Chu

Serial No.: 10/729,452

Group Art Unit: 1795

Filing Date: December 4, 2003

Confirmation No: 2060

Title: METHOD FOR PATTERNING A LOW ACTIVATION ENERGY PHOTORESIST

**AMENDMENT UNDER 37 CFR 1.114**  
**AND REQUEST FOR EXTENSION OF TIME**

Mail Stop RCE  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

This is a Request for Continued Examination in response to the final Office Action mailed from the PTO on April 10, 2008. A two-month extension of time is requested, and the fee therefor accompanies this response. Please amend the application as indicated herein.

The *Listing of the Claims* begins on page 2 of this document. Amendments to the claims are reflected therein. With this amendment, claim 22 has been canceled, and claims 1 and 24 have been amended.

*Remarks* begin on page 12 of this document.